

Si/Si-B/Si

(MBE)

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Characterization of Silicon-Boron slab doping in the Si/Si-B/Si structure grown by molecular beam epitaxy

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Abstract

Electrical characterization of Silicon-Boron slab doping in the Si/Si-B/Si structure grown by molecular beam epitaxy (MBE) has been considered in this paper. After growth, the transversal Hall voltage has been measured in the 60 - 300K temperature range and temperature dependence of Hall coefficient has been determined. The volume concentration and binding energy of dopant, Hall factor and lifting coefficient of Fermi level have been determined by theoretical simulation of hole sheet density versus temperature.

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100nm

(5 °A)

(B)

MODFET

()

()

p

(500 °C)

 10^{-10} mbar

(1 °A/s)

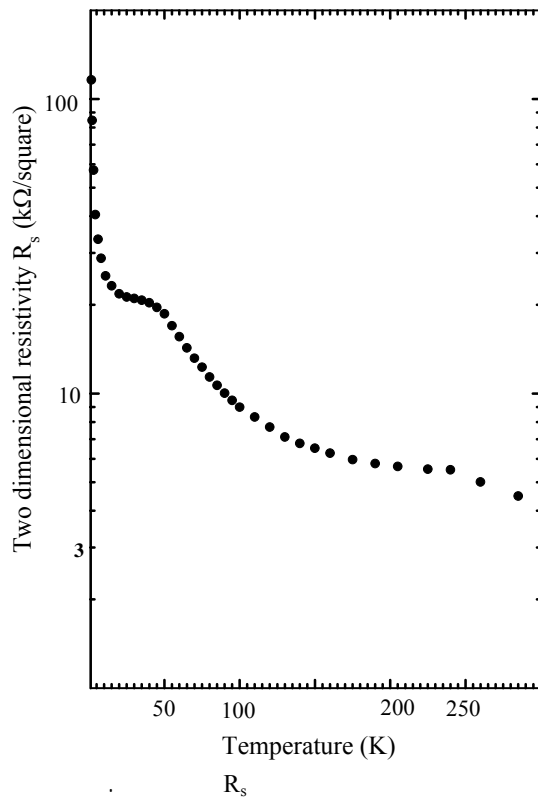
VG 90

Si/Si-B/Si

MBE

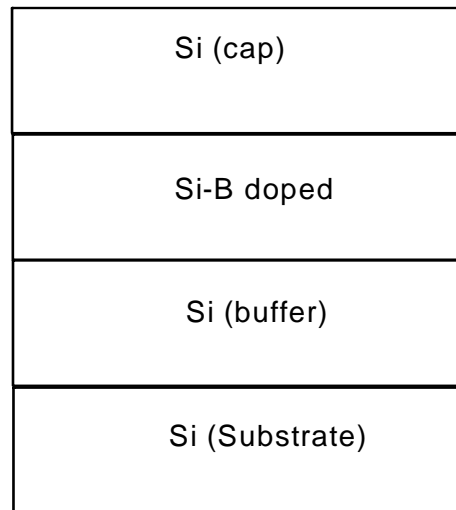
(1 μ m)

MBE
 1cm×1cm
 (10⁻⁵ mbar)
 1μm
 1mm
 Si-n (100)
 / mm
 550 °C
 500 °C
 HF
 Si-B
 Si
 B
 (shutter)
 Si
 B
 V_{xx} / K
 V_{xy}
 R_s
 R_H
 Si/Si-B/Si
 (substrate)
 (buffer)



L= 35nm
 Si-B 200nm
) 2×10²⁴ m⁻³ B
 Si (cap) (4.5×10²⁴ m⁻³)
 90nm

MODFET



Si/Si-B/Si

(L)

$$n_s = L N_A^- = \frac{L N_A}{1 + g \left(\frac{E_A - E_F}{kT} \right)} \quad ()$$

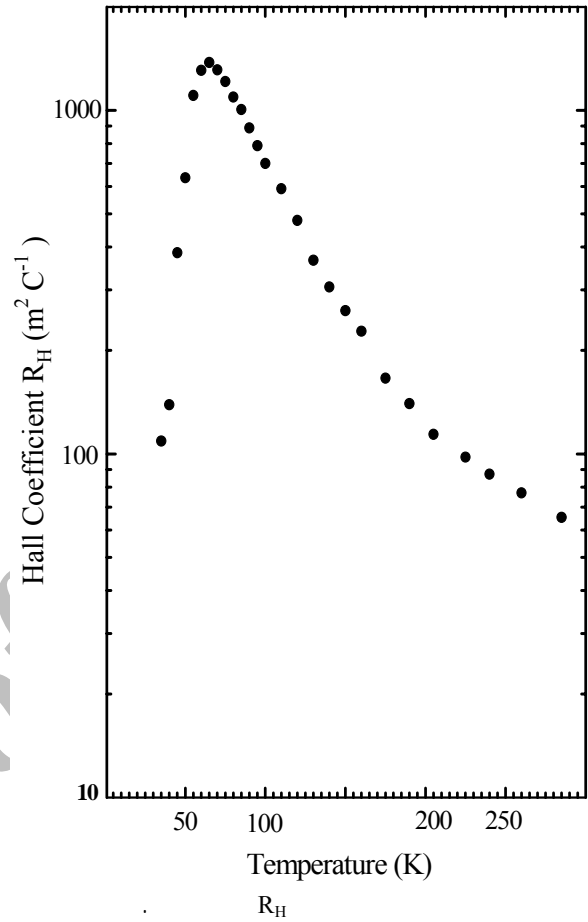
g N_A E_A E_F T k

$$E_F = C \times k_B T \ln \left(\frac{N_v}{N_A} \right) \quad ()$$

C N_v : []

$$N_v \equiv 2 \left[\frac{2\pi m_p kT}{h^2} \right]^{3/2} \quad ()$$

h m_p



< T < k

k

B < T < k

m_p n_s n_s

E_b

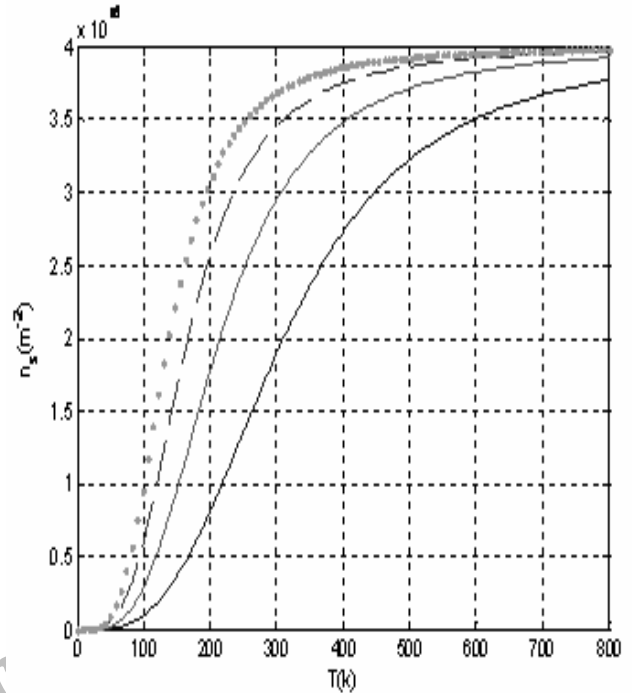
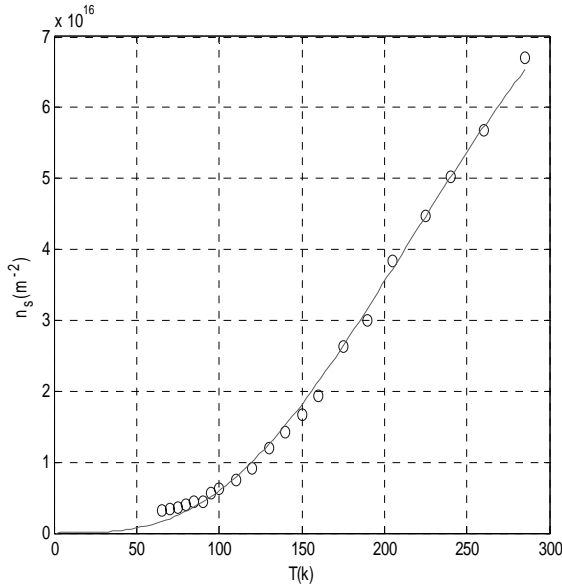
$$n_s = r_H \left(\frac{1}{e R_H} \right) \quad ()$$

r_H e

meV E_b -

[]

N_A^- ()



n_s ()
()

$N_A = 1 \times 10^{24} \text{ cm}^{-3}$ $E_b = 6 \text{ meV}$
 m_p / m_0 m_n / m_0 r_H

($L N_A = 10.8 \times 10^{16} \text{ m}^{-2}$) MBE %

nm
n Si

n_s C
T

E_b	N_A	m_p	C	r_H
6meV	$3.1 \times 10^{24} \text{ m}^{-3}$	$0.5 m_0$	1.88	0.7

[] Sadeghzadeh, M. A., et al. Appl. Phys. Lett. 74 (1999) 579-81.
 [] Myronov, M., et al. Appl. Phys. Lett. 80 (2002) 3117-9.
 [] Pearson, G. L. and Bardeen J., Phys. Rev. 75 (1949) 865-883.
 [] Joelson, K. B., et al. G. J. Appl. Phys. 81 (1997) 1265-9.